	1	****	O	L DB	Time stamp
1	Number	Hits 483	Search Text sputtering same (inline in-line)	DB USPAT	2003/03/11 08:22
2		483 79	sputtering same (inline in-line) same	USPAT	2003/03/11 08:51
1		2	(conventional well-known (well adj known))	USPAT	2003/03/11 08:51
3		3	spf-530h	USPAT	2003/03/11 08:31
4		0	spf-530h same (inline in-line)		
5		72		USPAT	2003/03/11 09:18
-		2	jp-08225936-\$.did.	USPAT;	2001/08/15 16:07
				US-PGPUB; EPO; JPO; DERWENT	
	ļ	13553	jp-08225936-\$.did.MITSUI-MASARU YAMAGATA	USPAT;	2001/08/15 16:14
-		13333	YAMAGATA-H YAMAGATA-HARUKI	US-PGPUB;	2001,00,13 10.11
			YAMAGATA-HARUYOSHI USHIDA USHIDA-M	EPO; JPO;	
				DERWENT	
l	ì		USHIDA-MASAO	i .	2001/08/15 16:15
-	i	13553	1 7 -	USPAT;	2001/08/15 16:15
İ			YAMAGATA-H YAMAGATA-HARUKI	US-PGPUB;	
			YAMAGATA-HARUYOSHI USHIDA USHIDA-M	EPO; JPO;	
	į		USHIDA-MASAO	DERWENT	
-		13551	MITSUI-MASARU YAMAGATA YAMAGATA-H	USPAT;	2003/03/10 08:49
			YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB;	
	į		USHIDA-M USHIDA-MASAO	EPO; JPO;	
1				DERWENT	·
-		4	((MITSUI-MASARU YAMAGATA YAMAGATA-H	USPAT;	2003/03/05 13:08
		_	YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB;	
			USHIDA-M USHIDA-MASAO) and (photomask adj	EPO; JPO;	
			blank)) and (substrate support) and (helium	DERWENT	
			"He")		
_		25	·	USPAT:	2003/03/05 13:06
-	1	2.3	YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB;	2003,03,03
-			USHIDA-M USHIDA-MASAO) and (photomask adj	EPO; JPO;	İ
1				DERWENT	
ļ		•	blank)	1	2002/03/28 15:17
[-		22	'L	USPAT;	2002/03/28 15:1/
Ì			support) and (helium "He")	US-PGPUB;	·
ĺ				EPO; JPO;	
				DERWENT	
-		603	(photomask blank phototool) and (substrate	USPAT;	2001/08/16 11:00
			support) and (helium "He") and (sputter	US-PGPUB;	•
			sputtering sputtered)	EPO; JPO;	
1				DERWENT	
-		63	((photomask blank phototool) and (substrate	USPAT;	2002/03/28 15:16
1			support) and (helium "He") and (sputter	US-PGPUB;	
			sputtering sputtered)) and (thin adj film)	EPO; JPO;	
			and (vacuum adj chamber)	DERWENT	
-		3548	(antireflective ARC) same (chromium adj	USPAT;	2001/08/16 11:22
ļ			nitride Cr?N?)	US-PGPUB;	·
1			·····•	EPO; JPO;]
1				DERWENT	
_		744	sputtering same (("ar" argon) and (helium	USPAT;	2001/08/16 11:57
		, 44	"He"))	US-PGPUB] , 3 - , ,
_		60	(((photomask blank phototool) and (substrate	USPAT;	2001/08/16 12:38
1		80	support) and (helium "He") and (sputter	US-PGPUB;	-552,55,15 12.56
			support; and (herium "He") and (sputter sputtering sputtered)) and (thin adj film)	EPO; JPO;	
			and (vacuum adj chamber)) not ((photomask	DERWENT	
			and (vacuum adj Chamber)) not ((photomask	DEKMENT]
			adj blank) and (substrate support) and		
			(helium "He"))	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	2007/05/25 22 52
-		263296	(430/5 430/322 430/320 428/\$ 427/\$).CCLS.	USPAT;	2001/08/16 12:41
				US-PGPUB;	1
				EPO; JPO;	· .
				DERWENT	
-		139		USPAT;	2001/08/16 12:49
			AND (PHOTOMASK MASK) AND ((SUBSTRATE	US-PGPUB;	
			SUPPORT) NEAR TRANSPARENT) AND (HELIUM	EPO; JPO;	
			"HE"?\$) AND (SPUTTER SPUTTERING SPUTTERED)	DERWENT]
-		260869	HE?\$(HEADLEY-J-L)	USPAT;	2001/08/16 12:48
				US-PGPUB;	1
				EPO; JPO;	1
				DERWENT	
_		702	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.)	USPAT;	2001/08/16 12:49
-		, , ,	AND (PHOTOMASK MASK) AND ((SUBSTRATE	US-PGPUB;	-302, 00, 20 12
			SUPPORT) NEAR TRANSPARENT) AND (SPUTTER	EPO; JPO;	1
				DERWENT	1
L			SPUTTERING SPUTTERED)	DEVMENT	

i				
-	442	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.)	USPAT;	2001/08/16 12:52
		AND (PHOTOMASK MASK) AND ((SUBSTRATE	US-PGPUB;	
		SUPPORT) NEAR TRANSPARENT) AND (HELIUM	EPO; JPO;	
		"HE"?\$5) AND (SPUTTER SPUTTERING SPUTTERED)	DERWENT	
] _	449	l	USPAT;	2001/08/16 12:58
		AND (PHOTOMASK MASK) AND ((SUBSTRATE	US-PGPUB;	
		SUPPORT) NEAR TRANSPARENT) AND (HELIUM	EPO; JPO;	
		"HE"?\$3) AND (SPUTTER SPUTTERING SPUTTERED)	DERWENT	
1	80		USPAT;	2002/03/28 15:16
-	00	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.)		2002/03/20 13:10
		AND (PHOTOMASK MASK) AND ((SUBSTRATE	US-PGPUB;	
		SUPPORT) NEAR TRANSPARENT) AND (HELIUM	EPO; JPO;	
	İ	"HE"?) AND (SPUTTER SPUTTERING SPUTTERED)	DERWENT	
- '	73	(((430/5 430/322 430/320 428/\$ 427/\$).CCLS.)	USPAT;	2001/08/16 13:07
		AND (PHOTOMASK MASK) AND ((SUBSTRATE	US-PGPUB;	
		SUPPORT) NEAR TRANSPARENT) AND (HELIUM	EPO; JPO;	
		"HE"?) AND (SPUTTER SPUTTERING SPUTTERED))	DERWENT	
		NOT ((photomask adj blank) and (substrate		
		support) and (helium "He"))		
_	92		USPAT;	2003/03/05 13:05
		AND (PHOTOMASK MASK) AND ((SUBSTRATE	US-PGPUB;	2000,00,00 =0,00
		SUPPORT) NEAR TRANSPARENT) AND (HELIUM	EPO; JPO;	
		"HE"?) AND (SPUTTER SPUTTERING SPUTTERED)	DERWENT	
			1 ' ' '	2003/03/05 13:05
-	78	((photomask blank phototool) and (substrate	USPAT;	2003/03/05 13:05
		support) and (helium "He") and (sputter	US-PGPUB;	
		sputtering sputtered)) and (thin adj film)	EPO; JPO;	1
		and (vacuum adj chamber)	DERWENT	
-	30	(photomask adj blank) and (substrate	USPAT;	2003/03/05 13:05
1		support) and (helium "He")	US-PGPUB;	
		••	EPO; JPO;	
			DERWENT	
_	1	ep-1022614-\$.did.	USPAT;	2002/03/28 15:25
		op 1022014 4.010.	US-PGPUB;	=====================================
			EPO; JPO;	
	_	/#5020220#\ PM	DERWENT	2002/02/20 15 25
-	1	("5830332").PN.	USPAT	2002/03/28 15:26
-	16	("3840451" "4417946" "4486286"	USPAT	2002/03/28 15:26
		"4529475" "4551216" "4620898"		
		"4624736" "4684436" "4822466"	!	1
		"4851097" "4913789" "4973345"		
		"5045165" "5073241" "5122249"	1	
		"5429730").PN.	1	
-	1	("4720442").PN.	USPAT	2002/03/28 15:36
-	5		USPAT	2002/03/28 15:43
		"4530891" "4563407").PN.	1	====, ==, ==
_	5	"4363846" "4374912" "4497878"	USPAT	2002/03/28 15:51
-	5		OSERI	2002/03/20 13.51
		"4530891" "4563407").PN.	HCDAE	2002/02/20 15 52
-	13	4720442.URPN.	USPAT	2002/03/28 15:52
-	37	((((430/5 430/322 430/320 428/\$	USPAT;	2002/03/28 16:19
	1	427/\$).CCLS.) AND (PHOTOMASK MASK) AND	US-PGPUB;	1
		((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND	EPO; JPO;	
		(HELIUM "HE"?) AND (SPUTTER SPUTTERING	DERWENT	
		SPUTTERED)) (((photomask blank phototool)	1	
		and (substrate support) and (helium "He")		
		and (sputter sputtering sputtered)) and		
		(thin adj film) and (vacuum adj chamber))		
		((photomask adj blank) and (substrate	[
		support) and (helium "He"))) and	1	
		support and (herrum "He")) and		
	227	1 ∸	HCDAT.	2002/02/20 16:20
_	331		USPAT;	2002/03/28 16:20
		(nitrogen "N2" "N.sub.2")	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	13	((sputtering) same (helium "He") same	USPAT;	2003/03/05 13:05
		(nitrogen "N2" "N.sub.2")) and (blank	US-PGPUB;	[
		photomask adj blank photoblank)	EPO; JPO;	
			DERWENT	
_	626	("He" Helium) same (chromium)	USPAT;	2002/03/28 16:35
	020	Control Cont	US-PGPUB;	,,
	ļ		EPO; JPO;	
	1			
1	1		DERWENT	

1				
-	28	(("He" Helium) same (chromium)) and (blank photomask adj blank photoblank)	USPAT; US-PGPUB; EPO; JPO;	2003/03/05 13:05
-	3	gb-2325473-\$.did. or ep-605814-\$.did.	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/03/05 12:12
-	93	((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/03/05 13:05
-	118	and (vacuum adj chamber)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/03/05 13:06
-	32	"HE"?) AND (SPUTTER SPUTTERING SPUTTERED) (("He" Helium) same (chromium)) and (blank photomask adj blank photoblank)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/03/05 13:06
-	16	((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/03/05 13:07
-	47	(photomask adj blank) and (substrate support) and (helium "He")	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/03/05 13:07
-	8	((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:07
-	31	(MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:07
-	26299	l	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:09
	9	(((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblank)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASARO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-HYAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-HYAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA "HE")) ((MITSUI-MASARU YAMAGATA YAMAGATA-HYAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA "YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:46
		USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (tensile adj stress)		

(([photomask blank phototool) and (substrate support) and (helium "He") and (sputter gputtering sputtered)) and (thin ad) film and (vacuum ad) chamber!) ((([430/5 alo)/322 alo) (vacuum ad) chamber!) ((([430/5 alo)/322 alo) (vacuum ad) chamber!) ((([430/5 alo)/322 alo) (vacuum ad) chamber!) ((([480/6 alo)/322 alo) (vacuum ad) chamber vacuum ad) blank photoblank) ((([480/6 alo) alo) (vacuum ad) chamber vacuum ad) blank photoblank) ((([480/6 alo) alo) alo) (([480/6 alo) alo) vacuum ad) blank photoblank) ((([480/6 alo) alo) alo) (([480/6 alo) alo) (([480/6 alo) alo) alo) (([480/6 alo) alo) (([480/6 alo) alo) (([480/6 alo) alo) alo) (([480/6 a	•				
(((photomask blank phototool) and (substrate support) and (helium "He") and (sputter Epo; JPo; sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((1430/5 430/322 430/320 428/5 427/5). CCLS.) AND (PHOTOMASK MASK) AND (SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblank)) (((sputtering) same (helium "He") same (introgen "N2" "N. sub.2")) and (blank photomask adj blank photoblank) ((((mitsul-MASGATA-HARGYASTA-HARGYASTA-HARGYAT			(((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblank)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (deposition adj rate)	US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:46
(substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (tensile adj stress)) - 0 605814.URPN. USPAT 2003/03/06 10:04		51	(((gb-2325473-\$.did. or ep-605814-\$.did.) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblank)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (deposition adj rate)) not (((gb-2325473-\$.did. or ep-605814-\$.did.) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) (("He" Helium) same (chromium)) and (blank photomask adj blank photoblank)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank	US-PGPUB; EPO; JPO;	2003/03/06 10:33
	-	0	(((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (tensile adj stress))	USPAT USPAT	2003/03/06 10:04 2003/03/06 10:05

-	4	(("4663183") or ("4728529")).PN.	USPAT;	2003/03/06 10:21
	!		US-PGPUB;	
·			EPO; JPO;	
			DERWENT	
-	252	flatness adj degree	USPAT;	2003/03/06 10:22
			US-PGPUB;	
1			EPO; JPO;	
			DERWENT	
-	4975	(blank photomask mask) and (thin adj film)	USPAT;	2003/03/06 12:47
		and (substrate support) and (helium "He")	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	3	((blank photomask mask) and (thin adj film)	USPAT;	2003/03/06 10:23
		and (substrate support) and (helium "He"))	US-PGPUB;	
		and (flatness adj degree)	EPO; JPO;	
			DERWENT	
-	154	((blank photomask mask) and (thin adj film)	USPAT;	2003/03/06 10:27
		and (substrate support) and (helium "He"))	US-PGPUB;	
1		and (tensile near stress)	EPO; JPO;	
[DERWENT	
. –	571552	(transition near metal) (chromium "Cr")	USPAT;	2003/03/06 10:32
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
1 -	60	(((blank photomask mask) and (thin adj film)	USPAT;	2003/03/06 10:33
		and (substrate support) and (helium "He"))	US-PGPUB;	
		and (tensile near stress)) and ((transition	EPO; JPO;	
		near metal) (chromium "Cr"))	DERWENT	

•				
_	52	(((gb-2325473-\$.did. or ep-605814-\$.did.)	USPAT;	2003/03/06 10:35
		(((photomask blank phototool) and (substrate	US-PGPUB;	
		support) and (helium "He") and (sputter	EPO; JPO;	
		sputtering sputtered)) and (thin adj film)	DERWENT	
		and (vacuum adj chamber)) (((430/5 430/322		İ
		430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK		
		MASK) AND ((SUBSTRATE SUPPORT) NEAR		
		TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER		
•		SPUTTERING SPUTTERED)) ((("He" Helium)		
		same (chromium)) and (blank photomask adj		
	1 .	blank photoblank)) (((sputtering) same		
		(helium "He") same (nitrogen "N2"		
		"N.sub.2")) and (blank photomask adj blank		
		photoblank)) ((photomask adj blank) and		
		(substrate support) and (helium "He"))		
		(((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		
		USHIDA-M USHIDA-MASAO) and (photomask adj		
		blank)) and (substrate support) and (helium		
		"He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		
		USHIDA-M USHIDA-MASAO) and (photomask adj		
		blank))) and (deposition adj rate)) not		
		(((gb-2325473-\$.did. or ep-605814-\$.did.)		
		(((photomask blank phototool) and (substrate		
		support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film)		
		and (vacuum adj chamber)) (((430/5 430/322		
		430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK		
		MASK) AND ((SUBSTRATE SUPPORT) NEAR		
		TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER		
		SPUTTERING SPUTTERED)) ((("He" Helium)		
		same (chromium)) and (blank photomask adj		
		blank photoblank)) (((sputtering) same		
		(helium "He") same (nitrogen "N2"		
		"N.sub.2")) and (blank photomask adj blank		
		photoblank)) ((photomask adj blank) and		
		(substrate support) and (helium "He")		
		(((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		
		USHIDA-M USHIDA-MASAO) and (photomask adj		
		blank)) and (substrate support) and (helium		
		"He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		
		USHIDA-M USHIDA-MASAO) and (photomask adj		
		blank))) and (tensile adj stress))		

	·, — — — — — — — — —		· · · · · · · · · · · · · · · · · · ·	
-	60	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2003/03/06 12:23
		film) and (substrate support) and (helium	US-PGPUB;	
		"He")) and (tensile near stress)) and	EPO; JPO;	
		((transition near metal) (chromium "Cr")))	DERWENT	
		not (((("4663183") or ("4728529")).PN.)		
1		(((blank photomask mask) and (thin adj film)		
		and (substrate support) and (helium "He"))		
		and (flatness adj degree))		
		((((gb-2325473-\$.did. or ep-605814-\$.did.)		
		(((photomask blank phototool) and (substrate		*
1		support) and (helium "He") and (sputter		
		sputtering sputtered)) and (thin adj film)		
		and (vacuum adj chamber)) (((430/5 430/322		
İ		430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK		
		MASK) AND ((SUBSTRATE SUPPORT) NEAR		
		TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER		
		· · · · · · · · · · · · · · · · · · ·		
	1	same (chromium)) and (blank photomask adj		
		blank photoblank)) (((sputtering) same		
		(helium "He") same (nitrogen "N2"		
		"N.sub.2")) and (blank photomask adj blank		
		photoblank)) ((photomask adj blank) and		
		(substrate support) and (helium "He"))		
		(((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		l i
		USHIDA-M USHIDA-MASAO) and (photomask adj		
		blank)) and (substrate support) and (helium		
		"He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		
		USHIDA-M USHIDA-MASAO) and (photomask adj		
	1	blank))) and (deposition adj rate)) not		
		(((gb-2325473-\$.did. or ep-605814-\$.did.)		
	1	(((photomask blank phototool) and (substrate		•
1		support) and (helium "He") and (sputter		
1		sputtering sputtered)) and (thin adj film)		
		and (vacuum adj chamber)) (((430/5 430/322		
		430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK		
1		MASK) AND ((SUBSTRATE SUPPORT) NEAR		
		TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER		
		SPUTTERING SPUTTERED)) ((("He" Helium)		
1		same (chromium)) and (blank photomask adj		
		blank photoblank)) (((sputtering) same		
		(helium "He") same (nitrogen "N2"		
1		"N.sub.2")) and (blank photomask adj blank		
1 .	1	photoblank)) ((photomask adj blank) and		
1		(substrate support) and (helium "He"))		
		(((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		
		USHIDA-M USHIDA-MASAO) and (photomask adj		
	1	blank)) and (substrate support) and (helium		
		"He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H		
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA		
		USHIDA-M USHIDA-MASAO) and (photomask adj		
		blank))) and (tensile adj stress))))		
-	150556	(tensile adj stress) (warp warping	USPAT;	2003/03/06 12:23
1	-	flatness)	US-PGPUB;	
			EPO; JPO;	
1			DERWENT	
-	6812	((tensile adj stress) (warp warping	USPAT;	2003/03/06 12:24
		flatness)) and (sputtering)	US-PGPUB;	
		·, · · · · · · · · · · · · · · · · ·	EPO; JPO;	
			DERWENT	
-	457	(((tensile adj stress) (warp warping	USPAT;	2003/03/06 12:25
	1	flatness)) and (sputtering)) and ((blank	US-PGPUB;	= 100, 10, 00 12.20
		photomask mask) and (thin adj film) and	EPO; JPO;	
		(substrate support) and (helium "He"))	DERWENT	
_	422			2003/03/06 12:48
_	432	((((tensile adj stress) (warp warping	USPAT;	2003/03/00 12:48
		flatness)) and (sputtering)) and ((blank	US-PGPUB;	
		photomask mask) and (thin adj film) and	EPO; JPO;	
	•	(substrate support) and (helium "He"))) and	DERWENT	
		(metal (transition near metal) chromium		
		chrome "Cr")	l	

-	5873	430/5.ccls.	USPAT;	2003/03/06 12:48
			US-PGPUB; EPO; JPO;	
1			DERWENT	
_	16	430/5.ccls. and ((((tensile adj stress)	USPAT;	2003/03/06 15:34
		(warp warping flatness)) and (sputtering))	US-PGPUB;	, ,
		and ((blank photomask mask) and (thin adj	EPO; JPO;	
		film) and (substrate support) and (helium	DERWENT	
		"He"))) and (metal (transition near metal)		
		chromium chrome "Cr"))	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	2002/02/06 15 54
-	41	(dc.m/c. adj power) near source	USPAT; US-PGPUB;	2003/03/06 15:54
			EPO; JPO;	
1			DERWENT	
_	19876	power adj density	USPAT;	2003/03/06 15:55
			US-PGPUB;	
			EPO; JPO;	
	1		DERWENT	
-	28		USPAT;	2003/03/06 16:40
		target)	US-PGPUB;	
			EPO; JPO; DERWENT	
_	0	 (dc.m/c. adj bias adj potential) same	USPAT;	2003/03/06 16:50
-		(graphite near target) same ("W" watts watt)	US-PGPUB;	2003,03,00 10.30
		\	EPO; JPO;	
			DERWENT	
-	408	(dc.u/c. adj power adj source) same ("W"	USPAT;	2003/03/06 16:57
		watts watt)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	0000/00/10 00 16
-	15071		USPAT;	2003/03/10 09:16
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO	US-PGPUB; EPO; JPO;	
		OSNIDA-M OSNIDA-MASAO	DERWENT	
-	1239	ROSASCO ROSASCO-S ROSASCO-STEPHAN	USPAT;	2003/03/10 08:59
		ROSASCO-STEPHEN ROSASCO-STEPHEN-D	US-PGPUB;	, ,
		ROSASCO-STEVE ROSASCO-STEVEN	EPO; JPO;	
			DERWENT	
_	18	••	USPAT;	2003/03/10 08:59
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB; EPO; JPO;	
		USHIDA-M USHIDA-MASAO) and (ROSASCO ROSASCO-S ROSASCO-STEPHAN ROSASCO-STEPHEN	DERWENT	
		ROSASCO-STEPHEN-D ROSASCO-STEVE	DUKARINI	
		ROSASCO-STEVEN)		
_	390		USPAT;	2003/03/10 09:17
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB;	
		USHIDA-M USHIDA-MASAO) and (helium "He")	EPO; JPO;	
		(NATMONIA MAGARINI MANAGARINI MAN	DERWENT	2002/02/20 22 2
	591	****	USPAT;	2003/03/10 09:17
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (helium "He"	US-PGPUB; EPO; JPO;	
		(inert adj gas))	DERWENT	
-	191		USPAT;	2003/03/10 09:18
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB;	
		USHIDA-M USHIDA-MASAO) and (helium "He"))	EPO; JPO;	
		and (metal)	DERWENT	
-	66		USPAT;	2003/03/10 09:18
		YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB;	
		USHIDA-M USHIDA-MASAO) and (helium "He")) and (metal)) and target	EPO; JPO; DERWENT	
_	4		USPAT;	2003/03/10 10:22
	1	YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA	US-PGPUB;	2000,00,10 10.22
		USHIDA-M USHIDA-MASAO) and (helium "He"))	EPO; JPO;	
		and (metal)) and target) and (vacuum near .	DERWENT	
		chamber)		
-	16095	sccm	USPAT;	2003/03/10 10:25
			US-PGPUB;	
			EPO; JPO; DERWENT	
L	L		DEKMENT	L

, -				
-	7	(direct adj current adj sputter) same	USPAT;	2003/03/10 10:27
		(vacuum inline in-line chamber power)	US-PGPUB;	
		· -	EPO; JPO;	
			DERWENT	
-	20	(direct adj current adj sputter) and	USPAT;	2003/03/10 11:55
		(vacuum inline in-line chamber power)	US-PGPUB;	
]		_ ·	EPO; JPO;	
			DERWENT	
-	13	((direct adj current adj sputter) and	USPAT;	2003/03/10 11:55
		(vacuum inline in-line chamber power)) not	US-PGPUB;	
		((direct adj current adj sputter) same	EPO; JPO;	
		(vacuum inline in-line chamber power))	DERWENT	
Í -	249	((tensile adj stress) (flatness near	USPAT;	2003/03/10 12:46
		degree)) same (helium He (inert))	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	19876	(power adj density) same (power)	USPAT;	2003/03/10 12:47
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	12	((power adj density) same (power)) same	USPAT;	2003/03/10 15:47
		(graphite adj target)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	(cm2) same (graphite adj target)	USPAT;	2003/03/10 13:04
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
] -	75	(cm2 cm inch in2 centimeter meter) same	USPAT;	2003/03/10 13:05
		(graphite adj target)	US-PGPUB;	
			EPO; JPO;	
	i		DERWENT	
-	2	jp-11012730-\$.did.	USPAT;	2003/03/10 15:08
			US-PGPUB;	
	1		EPO; JPO;	<u> </u>
			DERWENT	
-	1298	(silicon adj wafer) same transparent	USPAT;	2003/03/10 15:12
1	1		US-PGPUB;	
	1		EPO; JPO;	
		5	DERWENT	0000/00/50 55 55
-	3	spf-530H	USPAT;	2003/03/10 16:16
			US-PGPUB;	
	1		EPO; JPO;	
	30-	(DERWENT	2002/02/10 16:10
_	325	(sputtering adj power) same (rate)	USPAT;	2003/03/10 16:19
1			US-PGPUB;	
			EPO; JPO;	
1	240	(DERWENT	2002/02/11 00:20
	249	(sputtering adj power) same (rate)	USPAT	2003/03/11 08:20